

ABSTRACT OF THE DISCLOSURE

A UV-mask, a system and method for making the mask and a method of using the mask for producing an image a print medium are disclosed. The system includes a donor element having a substrate coated with a layer of IR-sensitive material and a layers of UV-absorbing material, and a receptor element. The IR-sensitive material is capable of detaching a significant portion of the itself and the UV-absorbing material from the donor element and transfer the detached materials to the receptor element when irradiated by an IR radiation. The method for making a UV-mask includes irradiating such a donor element with an IR radiation.

10 The method of using includes overlaying a digital UV mask on a UV-sensitive medium, exposing the medium to a UV radiation through the UV mask, and developing the UV-sensitive medium.

M2:20571754.01